

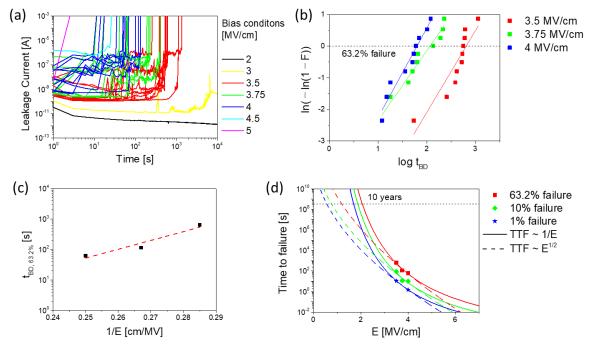
Supplementary Materials



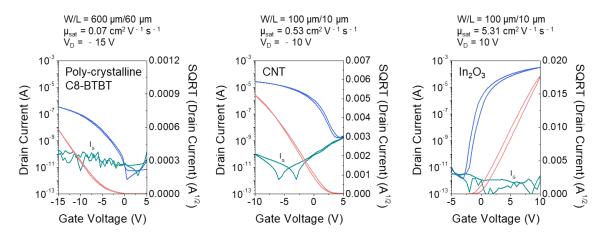
## Nanocluster-Based Ultralow-Temperature Driven Oxide Gate Dielectrics for High-Performance Organic Electronic Devices

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**Figure S1.** (a) Gate leakage current over time during a constant voltage stress for selected bias conditions of 2–5 MV/cm. (b)Weibull plot for the bias-dependent TDDB measurements conducted on nanocluster-based Al<sub>2</sub>O<sub>3</sub> dielectric films. (c) Weibull scaling factor ( $t_{BD}$  at 63.2% failure) from bias-dependent TDDB measurements as a function of 1/*E*. (d) Lifetime of the nanocluster-based Al<sub>2</sub>O<sub>3</sub> gate dielectric at lower gate voltages extrapolated from TDDB experiments. TTF for 63.2, 10, and 1% failure rate is shown. 1/*E* model (solid line) and  $E^{1/2}$  model (dotted line) were used to extrapolate the maximum operation voltage.



**Figure S2.** Representative transfer characteristics of poly-crystalline C8-BTBT, CNT, and indium oxide TFTs based on the nanocluster-based Al<sub>2</sub>O<sub>3</sub>.

**Table S1.** Summary of the extrapolated maximum operation voltages of the nanocluster-based Al<sub>2</sub>O<sub>3</sub> dielectric films comparing the lifetime models for 63.2, 10, and 1 % failure rate for 10 years lifetime.

Model (Failure Rate)	Maximum Operation Electric Field
1/E (63.2%)	2.07 MV/cm
1/E (10%)	1.88 MV/cm
1/E (1%)	1.69 MV/cm
E <sup>1/2</sup> (63.2%)	1.20 MV/cm
E <sup>1/2</sup> (10%)	0.75 MV/cm
E <sup>1/2</sup> (1%)	0.56 MV/cm



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